

# **FAST RECOVERY DIODES**

■ Junction Size: Square 180 mils

■ Wafer Size:

■ V<sub>RRM</sub> Class: 200 to 600 V

**Glassivated MOAT** Passivation Process:

■ Reference IR Packaged Part: 20ETF Series

# Major Ratings and Characteristics

Parameters		Units	Test Conditions	
V <sub>FM</sub>	Maximum Forward Voltage	1300mV	$T_J = 25^{\circ}C, I_F = 20 A$	
V <sub>RRM</sub>	ReverseBreakdownVoltageRange	200 to 600 V	T <sub>J</sub> = 25°C, I <sub>RRM</sub> = 100 μA	(1)

<sup>(1)</sup>Nitrogenflowondieedge.

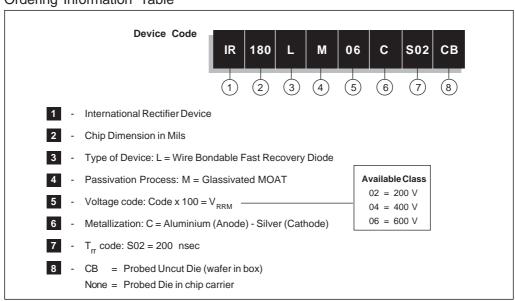
### Mechanical Characteristics

Nominal Back Metal Composition, Thickness	Cr-Ni-Ag (1 KA-4 KA-6 KA)	
Nominal Front Metal Composition, Thickness	100% AI, (20 µm)	
Chip Dimensions	180 x 180 mils (4.57 x 4.57 mm) - see drawing	
WaferDiameter	100 mm, with std. < 110 > flat	
WaferThickness	260 µm	
Maximum Width of Sawing Line	45µm	
Reject Ink Dot Size	0.25mmdiameter minimum	
InkDotLocation	Seedrawing	
Recommended Storage Environment	Storage in original container, in dessicated nitrogen, with no contamination	

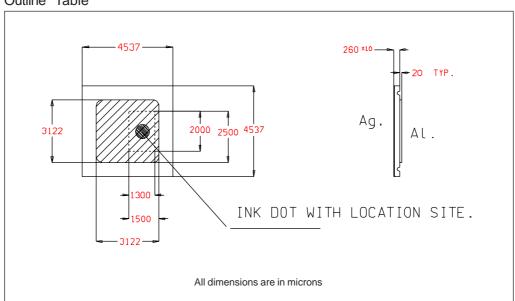
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# Ordering Information Table



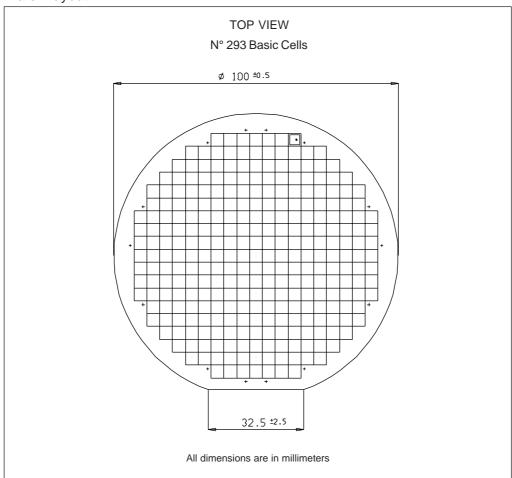
# Outline Table



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# Wafer Layout



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